

Notice of References Cited		Application/Control No. 09/103,873	Applicant(s)/Patent Under Reexamination NAGANO ET AL.	
		Examiner José R Diaz	Art Unit 2815	Page 1 of 1

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	B	US-5,750,419	05-1998	Zafar, Sufi	438/3
	C	US-5,624,864	04-1997	Arita et al.	438/3
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	M	US-			

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NON-PATENT DOCUMENTS

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	U	Fundamentals of Chemical of Chemical Vapor Deposition. TEOS / OZONE Thermal CVD. Film Quality: Moisture, Stress, Cracking. Tutorial [online]. TimeDomain CVD Inc., 2002 [retrieved on 2004-02-18]. Retrieved from the Internet: < URL:
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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